

Notice of References Cited

Application No.

08-846671

Applicant(s)

Ko

Examiner

George Goudreau

Group Art Unit

1763

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U.S. PATENT DOCUMENTS

*	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS
A					
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D					
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L					
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N	56-114,355	9-8-81	Japan	Yoji		
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X		

* A copy of this reference is not being furnished with this Office action.
(See Manual of Patent Examining Procedure, Section 707.05(a).)